

(b) Amendments to the Claims

Please amend claim 10 as follows. A detailed listing of all the claims that are or were on the application is provided.

1. - 9. (Cancelled)

10. (Currently Amended) A method of forming a deposited film in a system having:

(i) a source for supplying a source gas into a chamber for forming a deposited film on a substrate;

(ii) a plurality of shut-off valves provided in series between a non-reactive gas source and the chamber for introducing a non-reactive gas into the chamber for returning pressure within the chamber to atmospheric pressure; ~~and~~

(iii) ~~at least one of~~ a pressure gauge; and ~~or~~

(iv) an evacuating means provided between the plurality of shut-off valves, comprising:

(a) detecting gas leakage in the shut-off valves by reducing pressure between the plurality of shut-off valves to facilitate detection of gas leakage in the shut-off valves;

(b) closing the plurality of shut-off valves; and

(c) while the shut-off valves are closed, supplying the source gas into the chamber to form the deposited film.

11. (Previously Presented) The method according to claim 10, wherein a space between the plurality of shut-off valves is filled with the non-reactive gas to perform film deposition.